

MATERIAL	Toxic Rating		RF/DC	Power %	Bias (V)	O2 flow (sccm)	Ar flow (sccm)	Temperature (°C)	Pressure (mT)	Expected rate (nm/min)	Measured rate (nm/min)	Method
	1 to 5	Gun										
Al2O3	2	6	RF	50			20	18	3		1.55	Filmtek
AlN	1	1	RF	50	354		20	18	4	1.5		
BN	1	6	RF	50	378		20	18	4			
CaF2	2	5	RF	45	130		20	24	4	1.08	2.22	STYLUS
Er2O3	2	6										
GeO2	1	5	RF	25		10	10	18	4		0.85	ELLIP
			RF	50		10	10	18	4		2.35	ELLIP
			RF	50		15	5	18	4		2.66	ELLIP
HfO2	2	5										
ITO/SnO2	1	1	RF	10		0	20	18	1.5		1.4	ELLIP/Sty
ITO/SnO2	1	5	RF	40	115	10	10	18	4		1.66	ELLIP/Sty
MgF2 NC	2	5 or 6	RF	50	265		20	18	3		3.26	Ellip
MgF2	2	5 or 6	RF	45			20	18	4		0.52	Deketk
MgO	2	5	RF	50			20	18	3		0.38	
NiO		2	DC	20	390	2	18	18	4	-	13	Stylus
SnO2	3											
Si3N4	1	6	RF	50			20	18	3	1.3	1.77	STYLUS
SiO2	1	1	RF	50			20	18	4	2	1.71	RBS
		1	RF	50	419		20	300	4		1.43	STYLUS
TaO2												
TeO2	3	5										
TiN	2	3	DC	20	590	N2- 5.5	25	18	2.5		1.6	Film Tek
			DC	20	540	0	20	18	2.5		1.72	Film Tek
TiW	2											
TiO2	1	5	RF	50	149		20	18	3	1.25	1.08	Film tek
TiO2	1	1	DC	20	420		20	18	4		1.44	Filmtek
WSi2	2	1 or 5 or 6										
ZnO	3	1 or 5 or 6	RF	50	135		20	600	4		4.66	STYLUS
	3	1 or 5 or 6	RF	50	126		20	18	4		3.33	STYLUS
	3	1 or 5 or 6	RF	30	215		20	350	1.5		1.5	STYLUS
	3	1 or 5 or 6	RF	30	215	2	18	350	1.5		1.4	STYLUS

